



DOCKET NO.: 0039-7632-0X

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

HIROYUKI YANO ET AL

: EXAMINER: DEO, D.V.

SERIAL NO: 09/531,163

:

FILED: MARCH 17, 2000

: GROUP ART UNIT: 1765

FOR: AQUEOUS DISPERSION,
AQUEOUS DISPERSION FOR
CHEMICAL MECHANICAL
POLISHING USED FOR
MANUFACTURE OF
SEMICONDUCTOR DEVICES,
METHOD FOR MANUFACTURE
OF SEMICONDUCTOR DEVICES,
AND METHOD FOR FORMATION
OF EMBEDDED WIRING

#35/G
8/4/03
RECEIVED
AUG 01 2003
TC 1765

REQUEST FOR RECONSIDERATION

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

Responsive to the Office Action of April 30, 2003, Applicants respectfully request reconsideration of the above-identified application in view of the following amendment and remarks.

IN THE CLAIMS

Please cancel Claims 61-80.

Please add the following new claims.

81. (New) A dispersion comprising polymer particles, inorganic particles and water, wherein the zeta potential of said polymer particles and the zeta potential of said inorganic

G1